

5. (amended) The method of claim 1 wherein the sensitizer is a heteroaromatic compound.

*B7  
C07*  
6. (amended) The method of claim 1 wherein the sensitizer has from 1 to 3 separate or fused rings.

*B5  
B6  
B7  
C07*  
7. (amended) The method of claim 1 wherein the photoacid generator compound is an onium compound or a non-ionic compound.

*B5  
B6  
B7  
C07*  
8. (amended) The method of claim 1 wherein the photoacid generator compound is an iodonium or sulfonium photoacid generator compound which has one or more cation substituents selected from the group consisting of optionally substituted naphthyl, optionally substituted thienyl and pentafluorophenyl.

*B2  
B3*  
10. (amended) The method of claim 1 wherein the photoacid generator compound is a non-ionic oxime sulfonate compound or a non-ionic N-oxyimidatosulfonate compound.

*B2  
B3*  
11. (amended) The method of claim 1 wherein the photoacid generator is a compound of any one of Formula I through XIV, XIVA, XV, XVIA, XVIB, XVIB', XVIC, XVIC', XVICa, XVICb, and XVICc.

12. (amended) The method of claim 1 wherein the photoresist coating layer is exposed to radiation having a wavelength of about 193 nm.

13. A photoresist composition comprising a resin and a photoacid generator system, the system comprising a sensitizer compound and a photoacid generator compound that is 1) an iodonium or sulfonium photoacid generator compound which has one or more cation